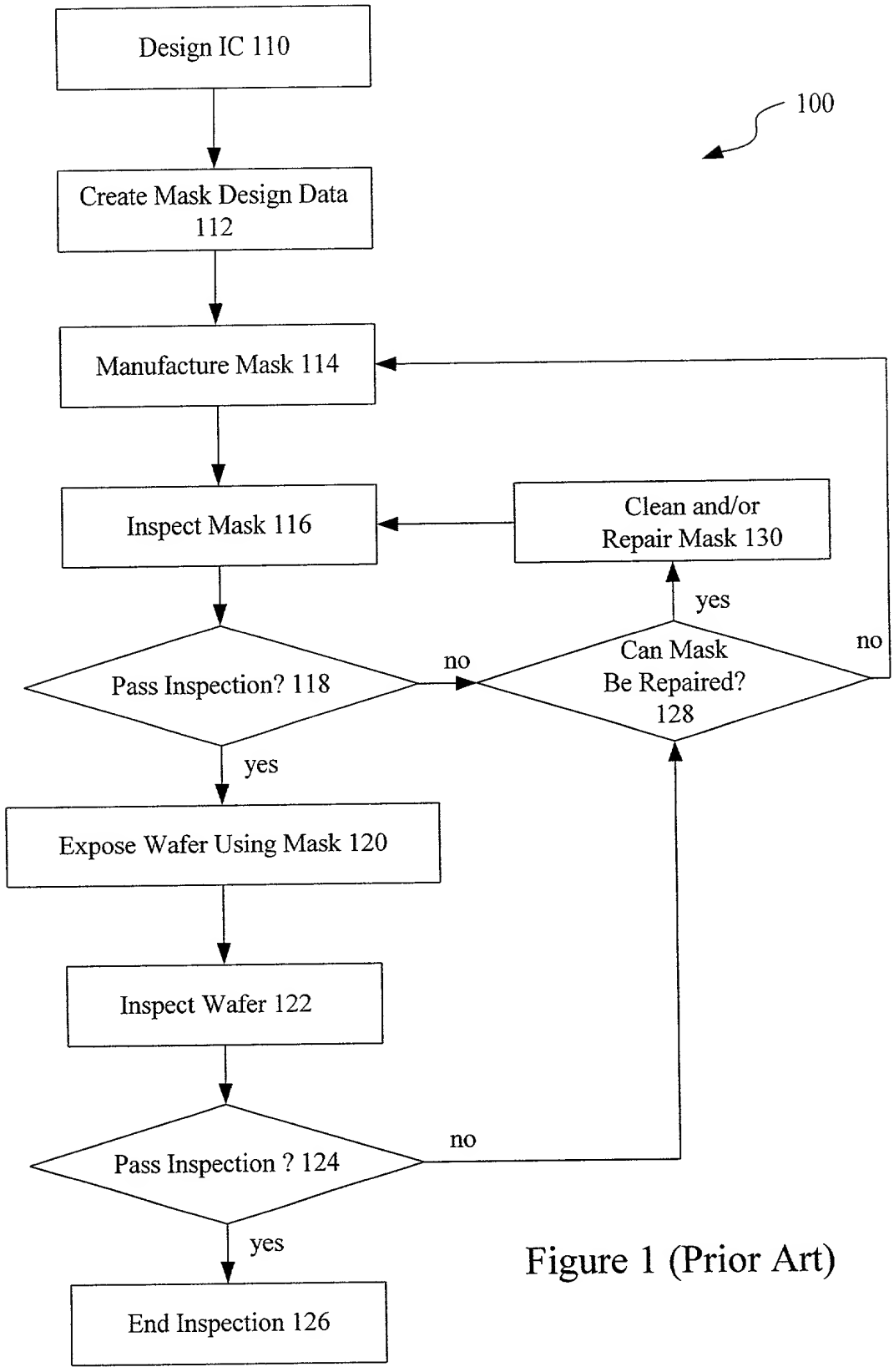


Figure 1 (Prior Art)

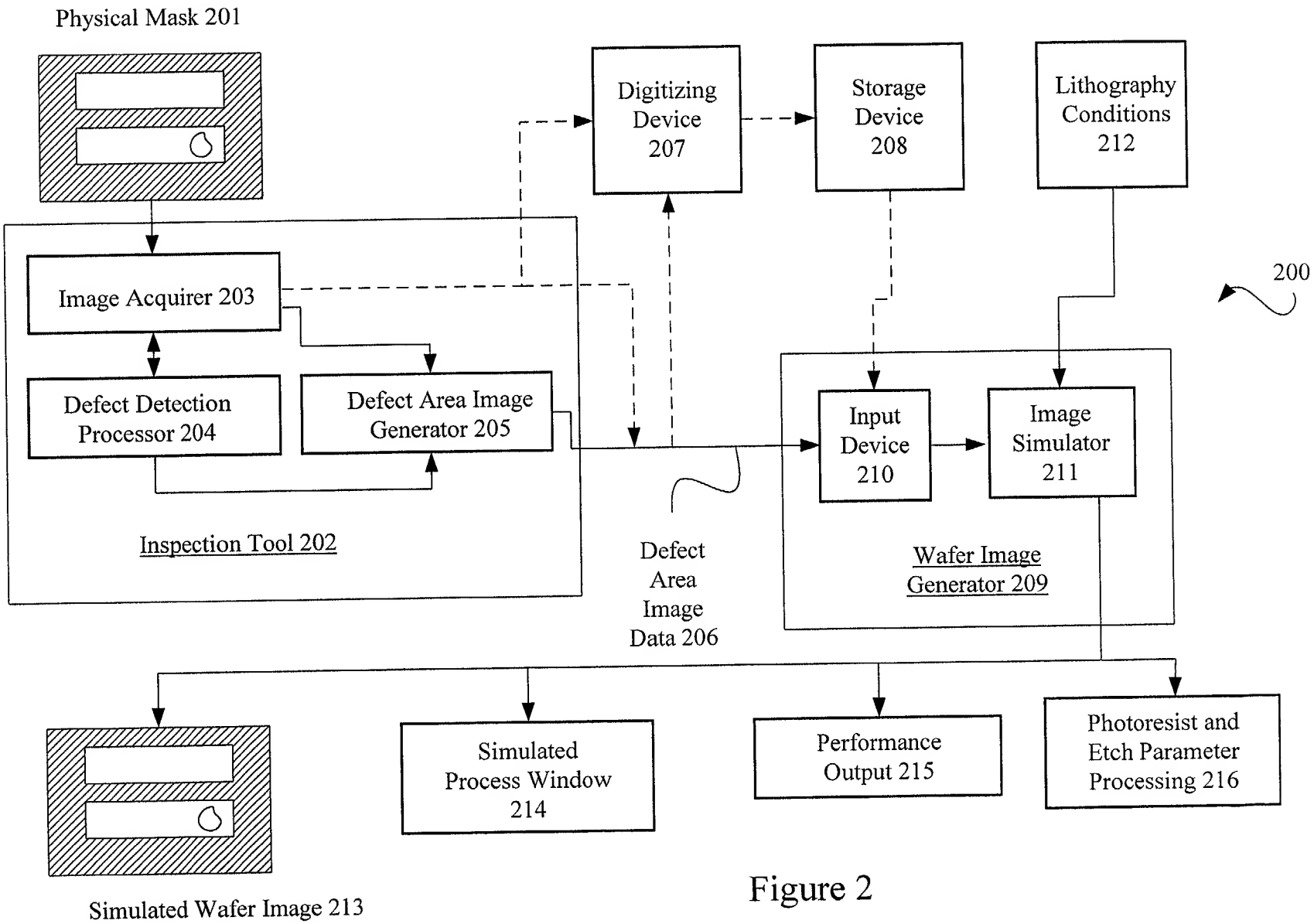
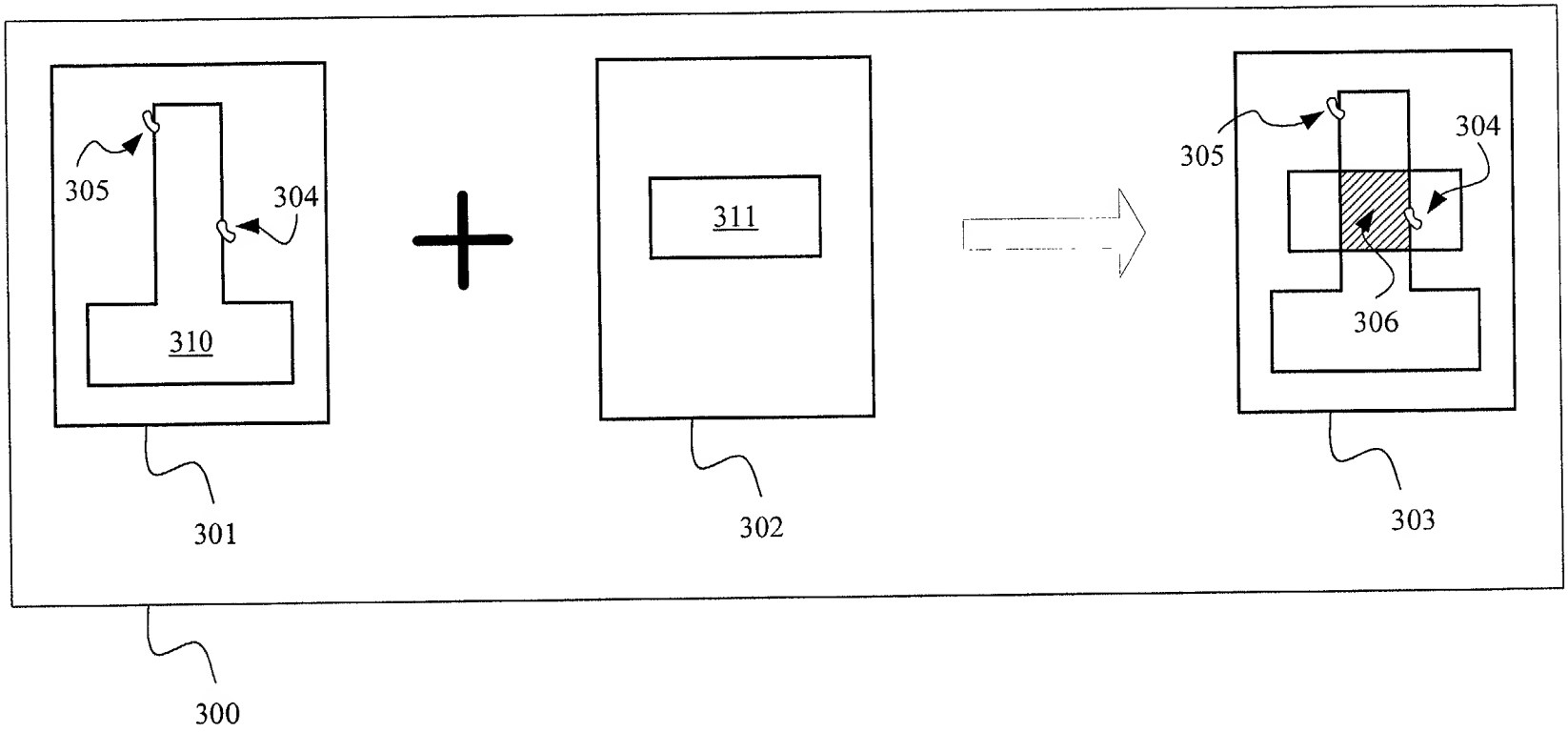

Physical Mask 201
Digitizing Device 207
Storage Device 208
Lithography Conditions 212
200
Image Acquirer 203
Defect Detection Processor 204
Defect Area Image Generator 205
Inspection Tool 202
Defect Area Image Data 206
Input Device 210
Image Simulator 211
Wafer Image Generator 209
Simulated Process Window 214
Performance Output 215
Photoresist and Etch Parameter Processing 216
Simulated Wafer Image 213

Figure 2



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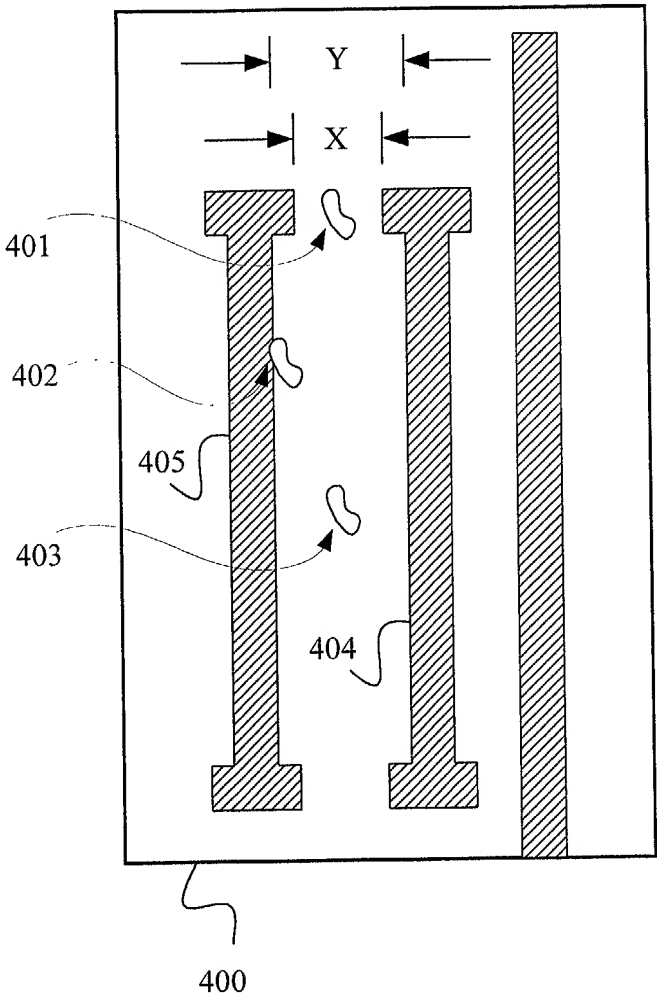


Figure 4A

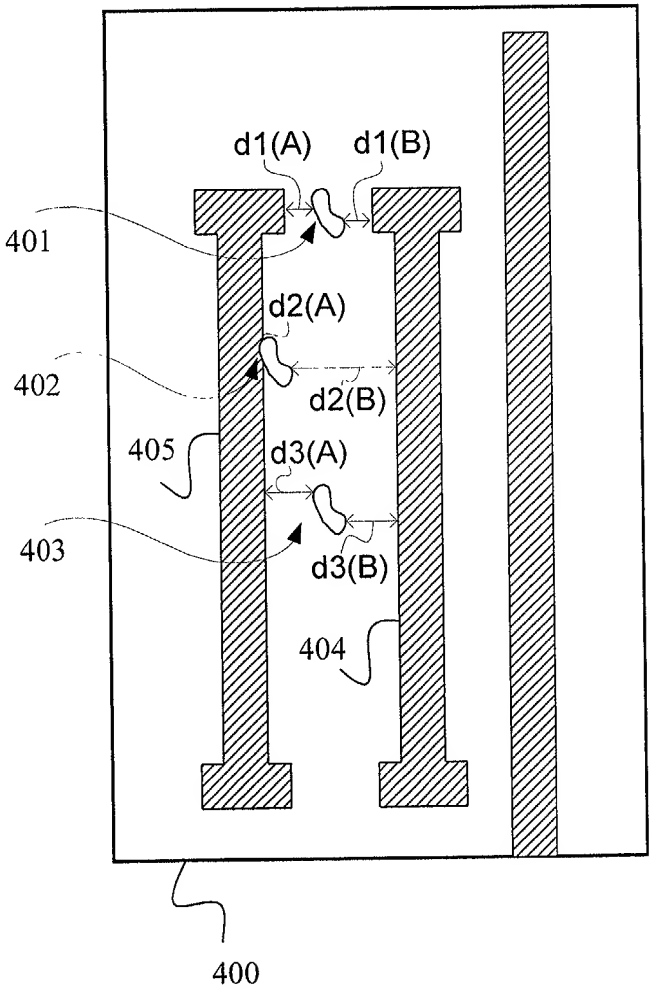
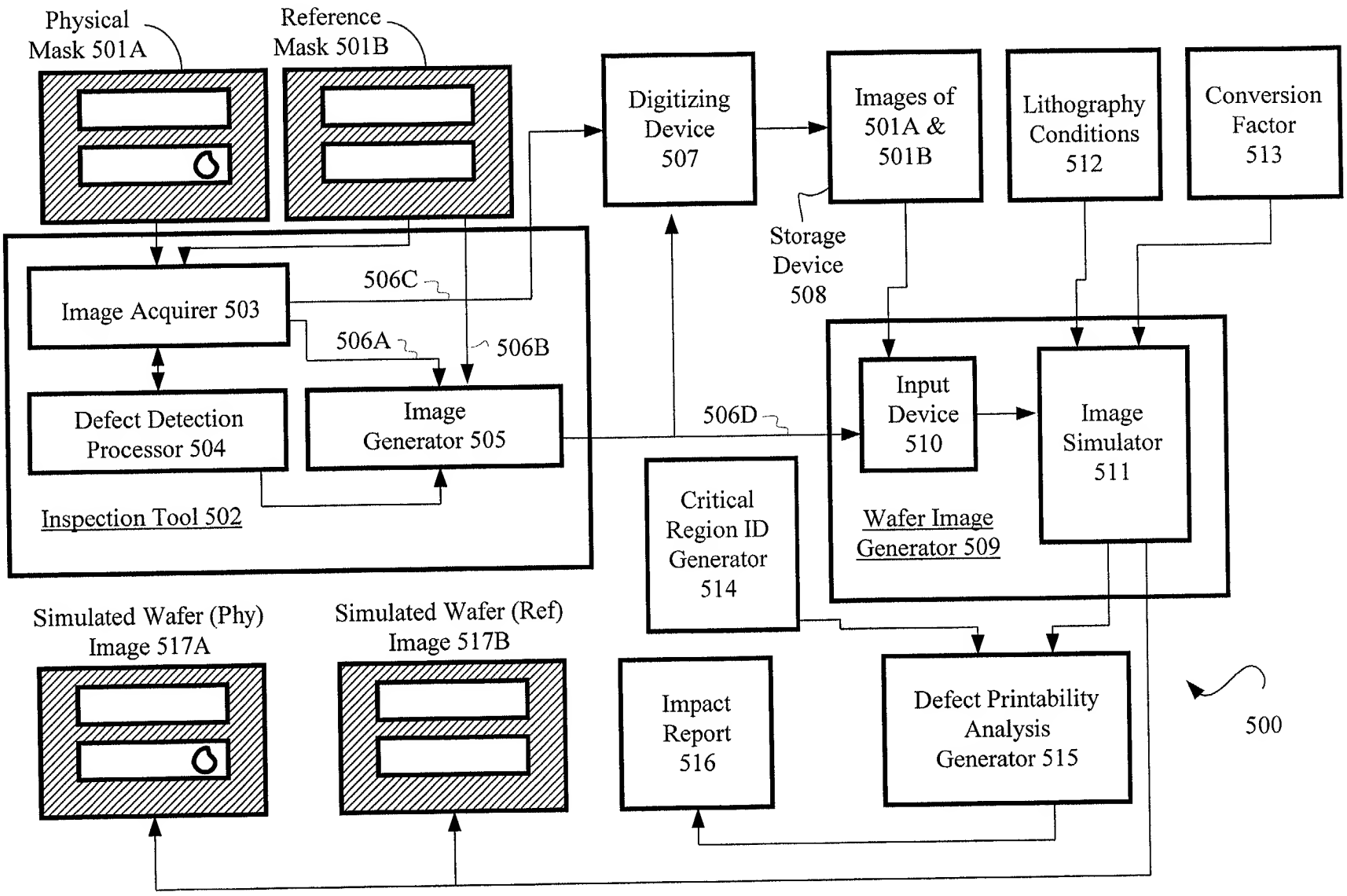


Figure 4B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Reference Mask 501B
Digitizing Device 507
Images of 501A & 501B
Lithography Conditions 512
Conversion Factor 513
Storage Device 508
Image Acquirer 503
506C
506A
506B
Defect Detection Processor 504
Image Generator 505
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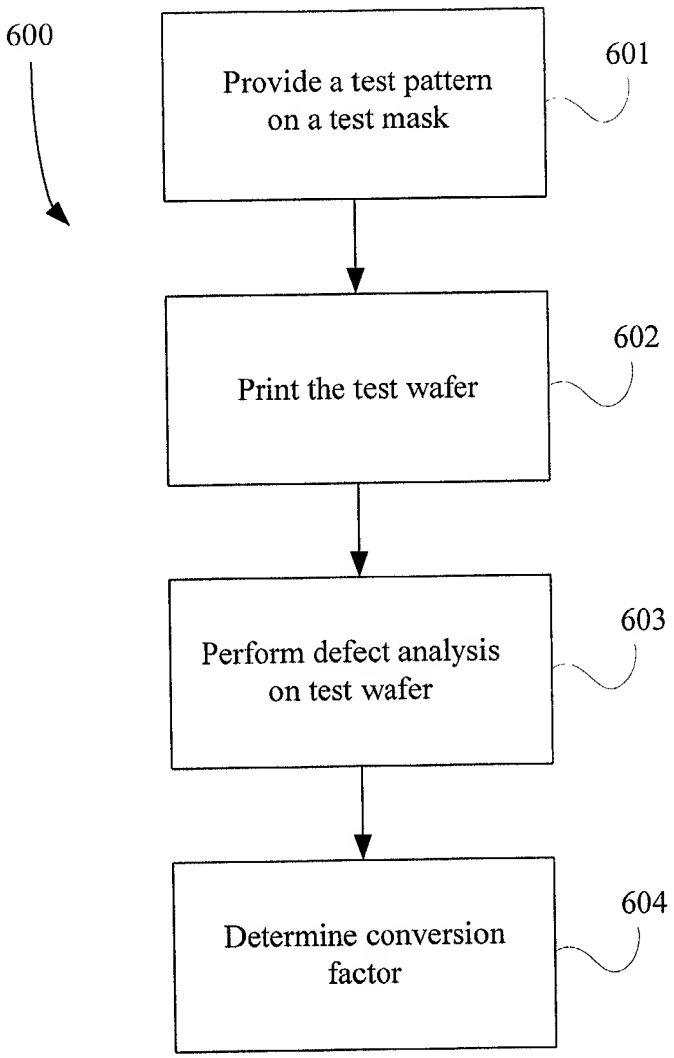
506D
Input Device 510
Image Simulator 511
Wafer Image Generator 509
Critical Region ID Generator 514
Simulated Wafer (Phy) Image 517A
Simulated Wafer (Ref) Image 517B
Impact Report 516
Defect Printability Analysis Generator 515
500

Figure 5



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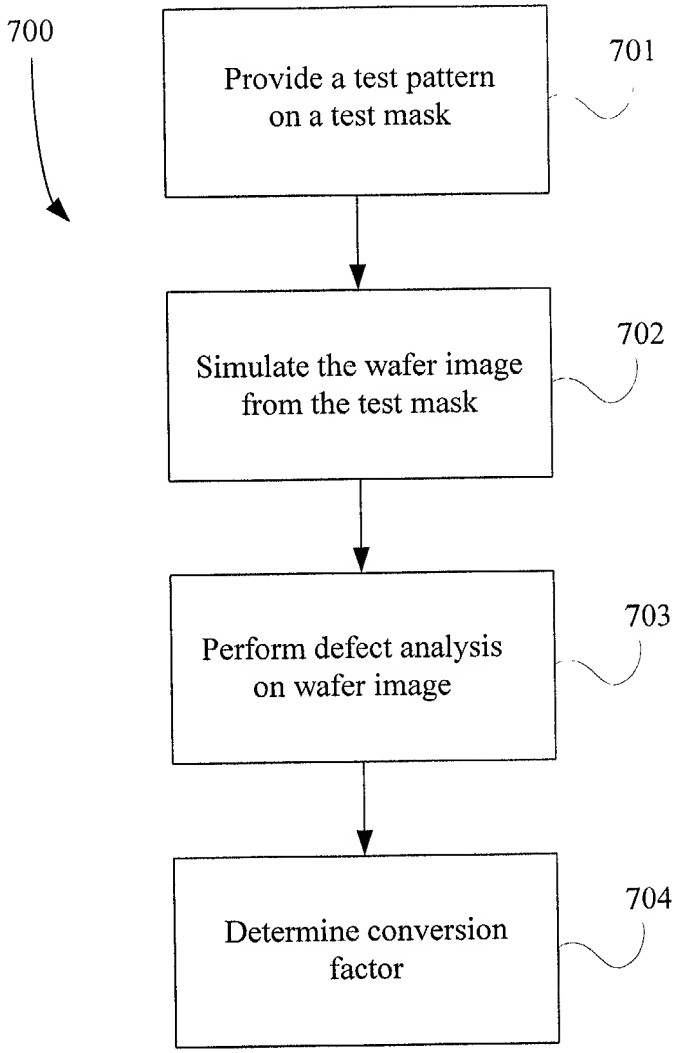


Figure 7

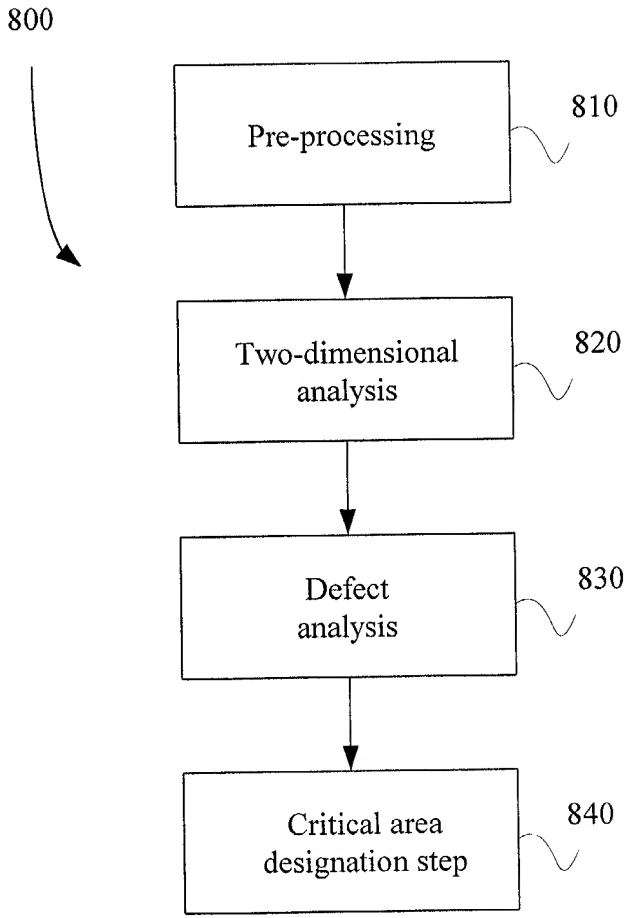


Figure 8A

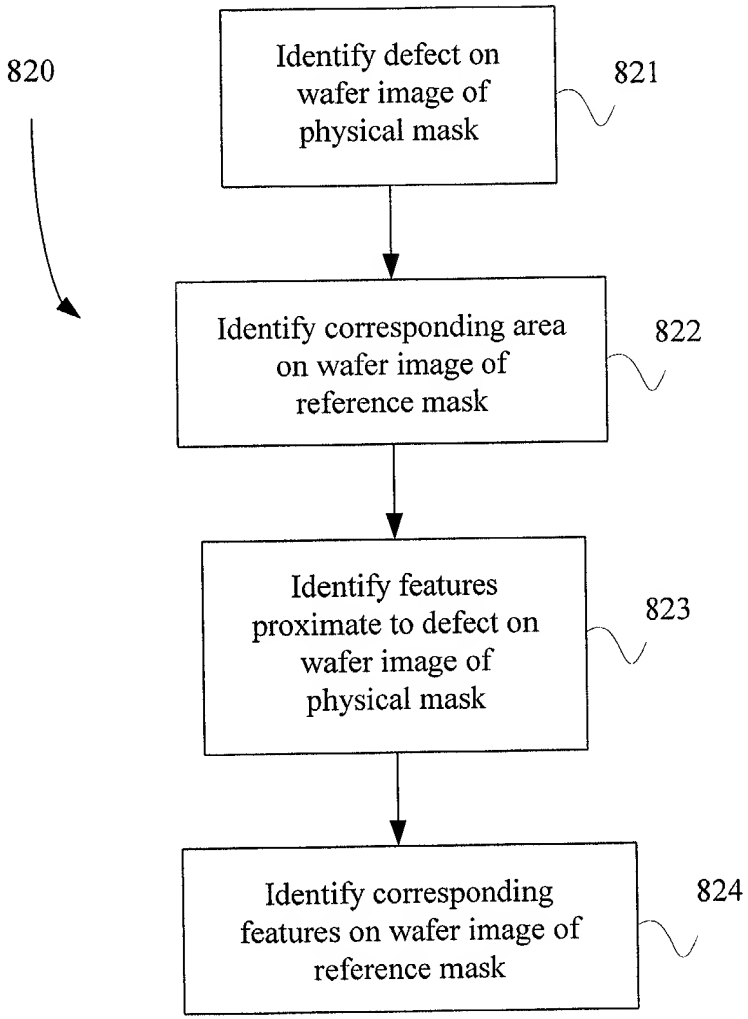


Figure 8B

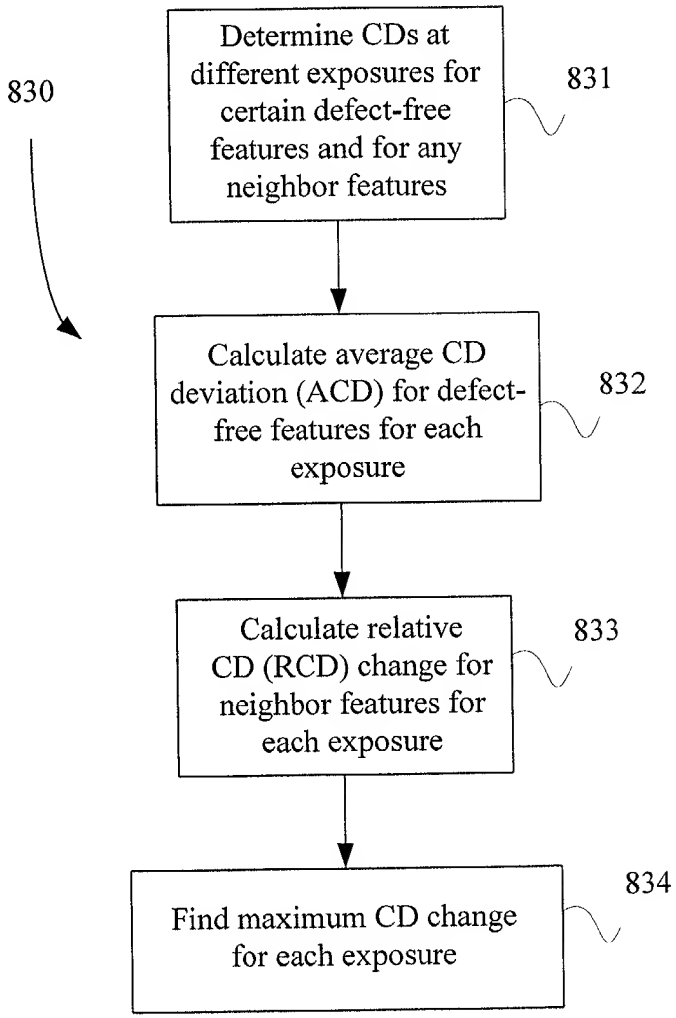


Figure 8C

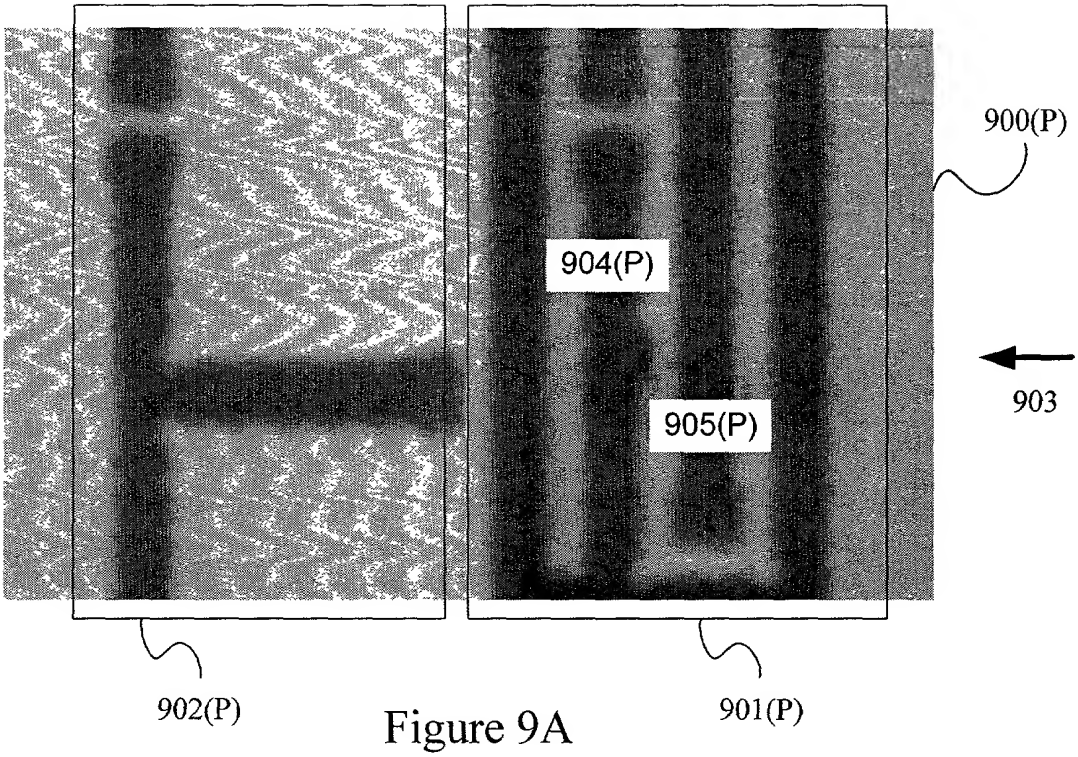


Figure 9A

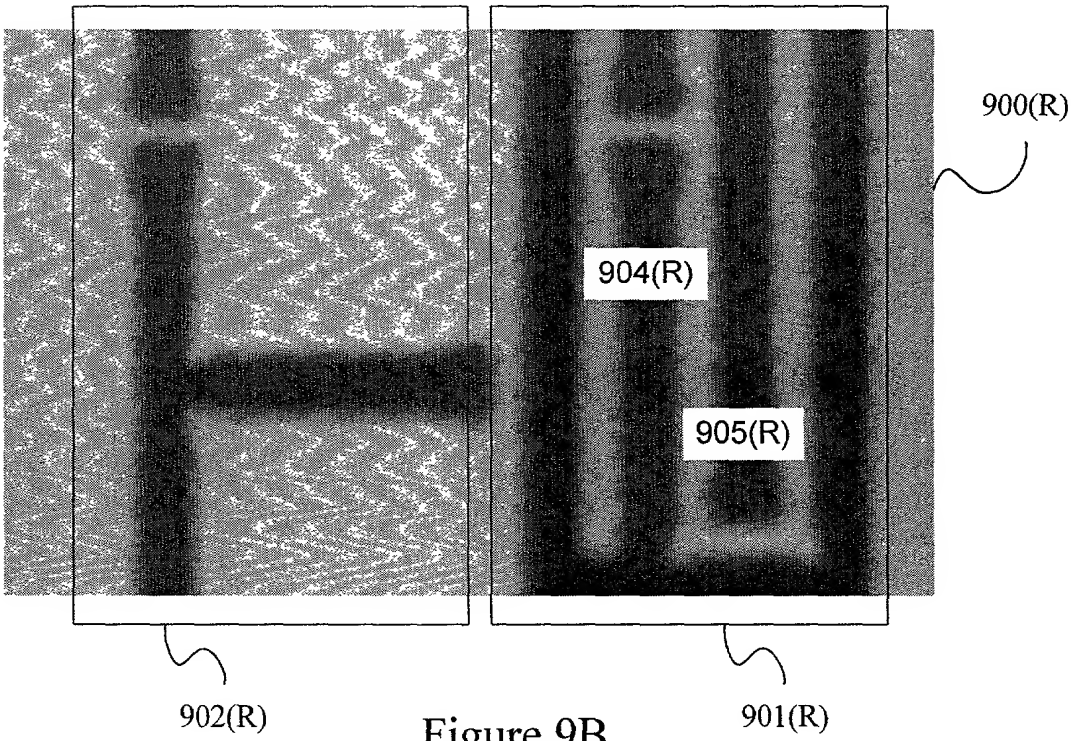


Figure 9B

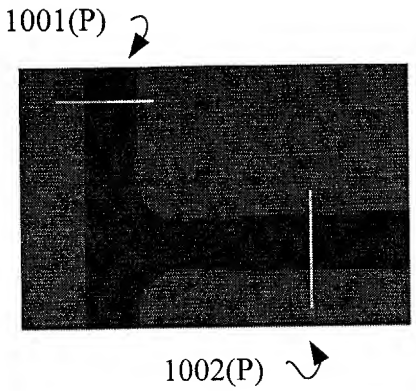


Figure 10A(1)

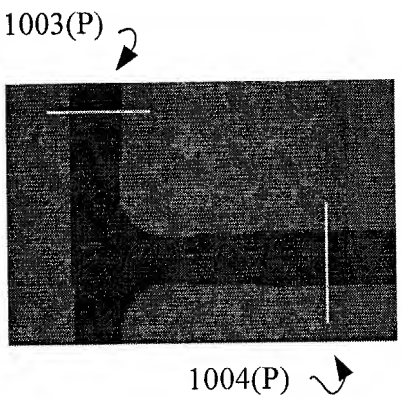


Figure 10A(2)

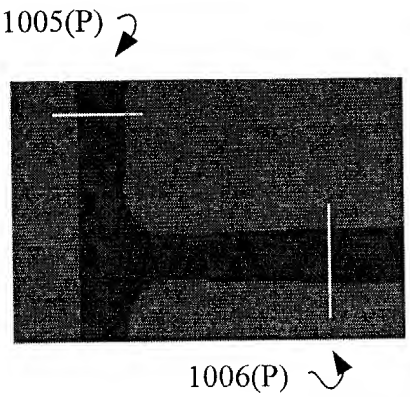


Figure 10A(3)

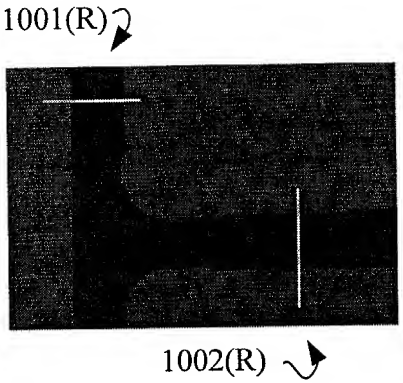


Figure 10B(1)

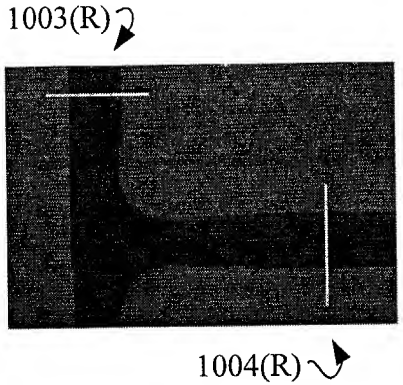
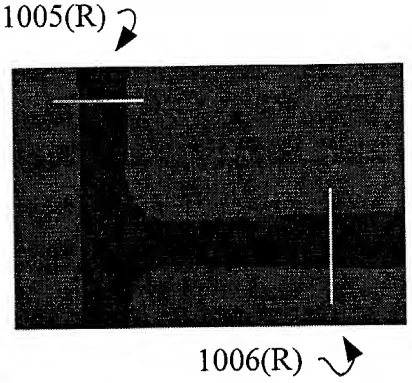


Figure 10B(2)



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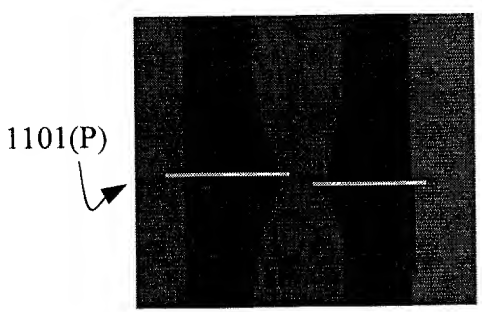


Figure 11A(1)

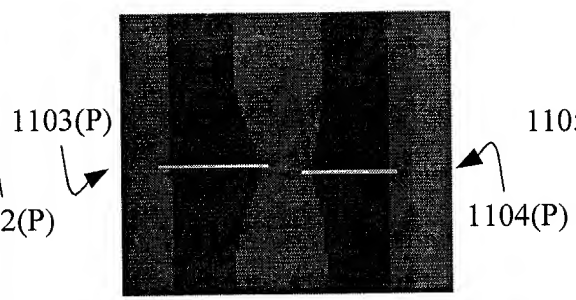
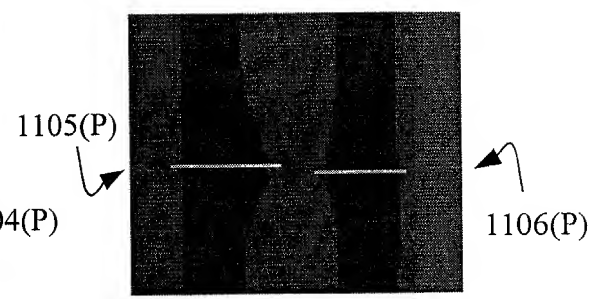


Figure 11A(2)



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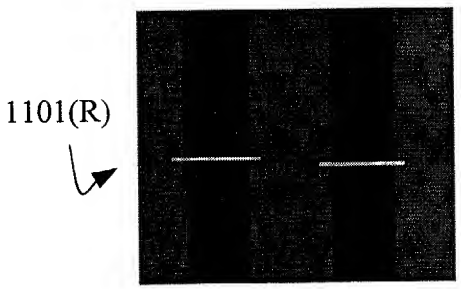
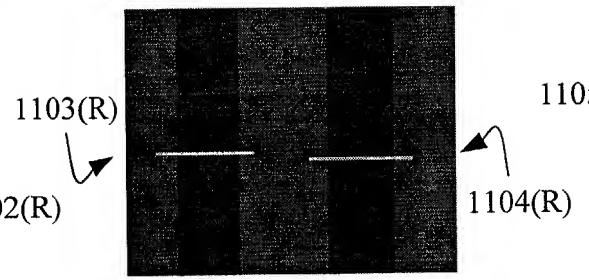


Figure 11B(1)



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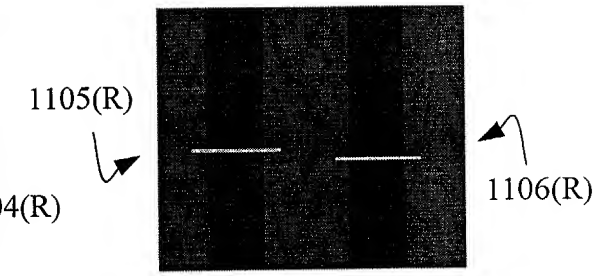


Figure 11(3)

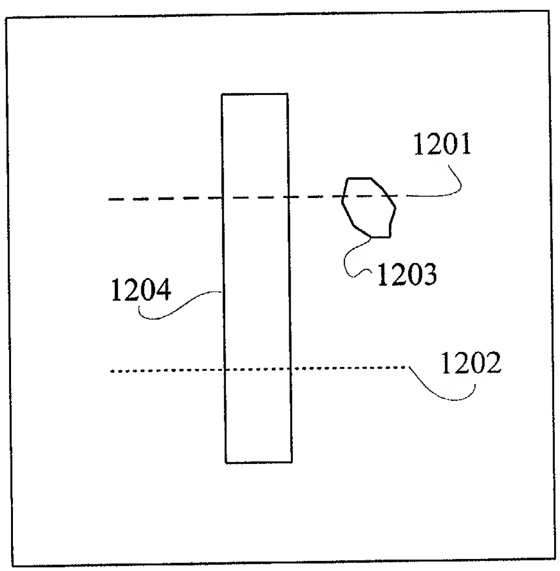


Figure 12A

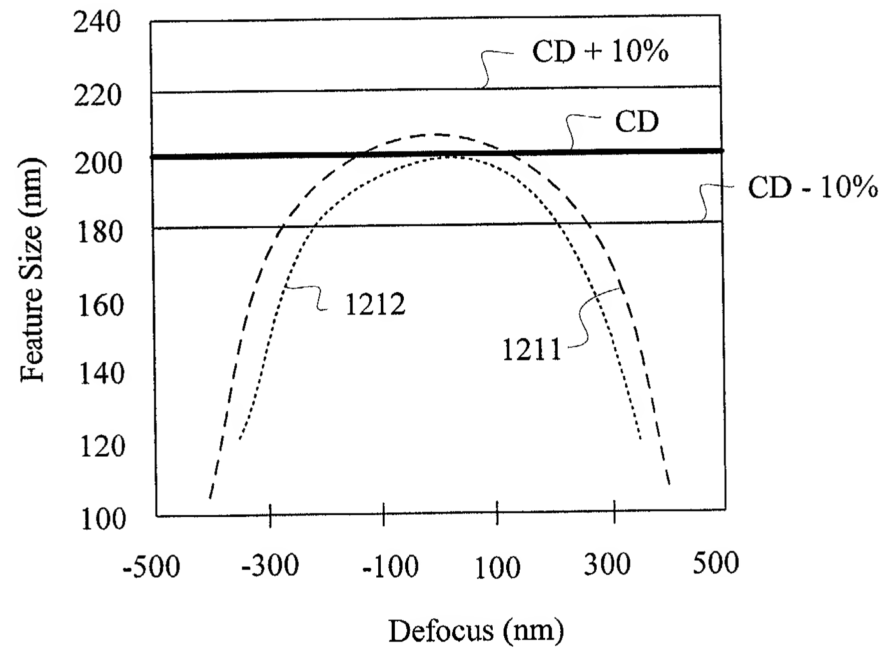


Figure 12B

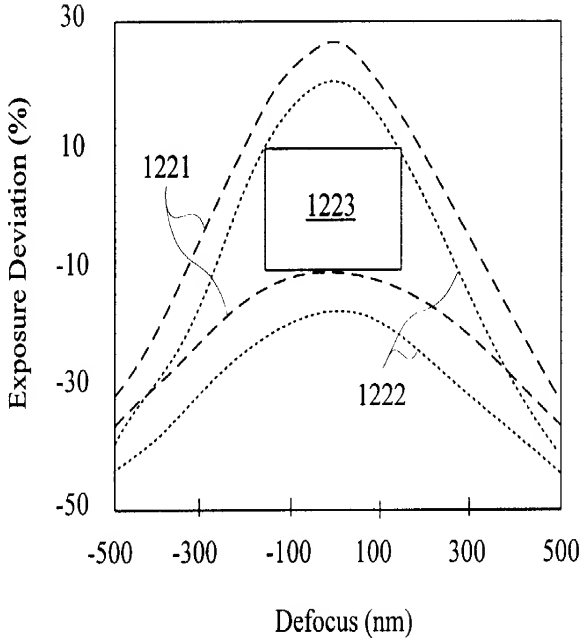


Figure 12C

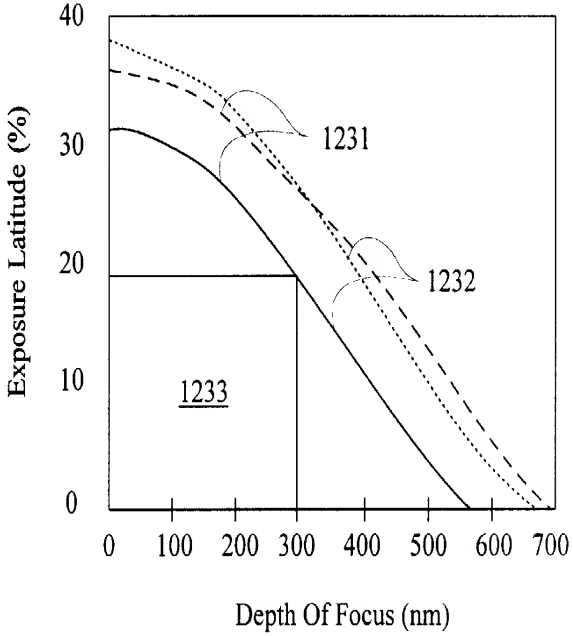


Figure 12D

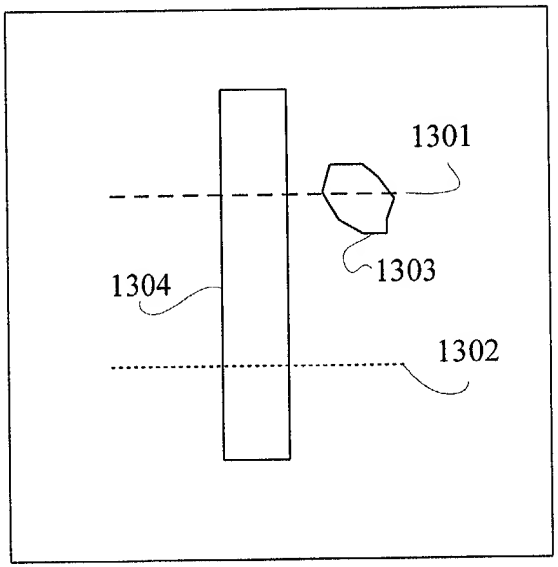


Figure 13A

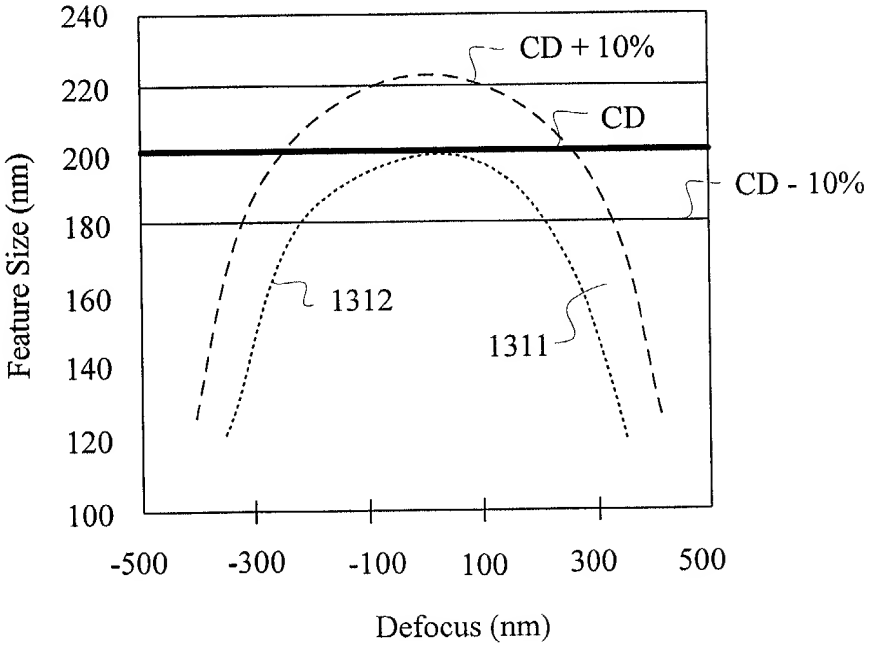
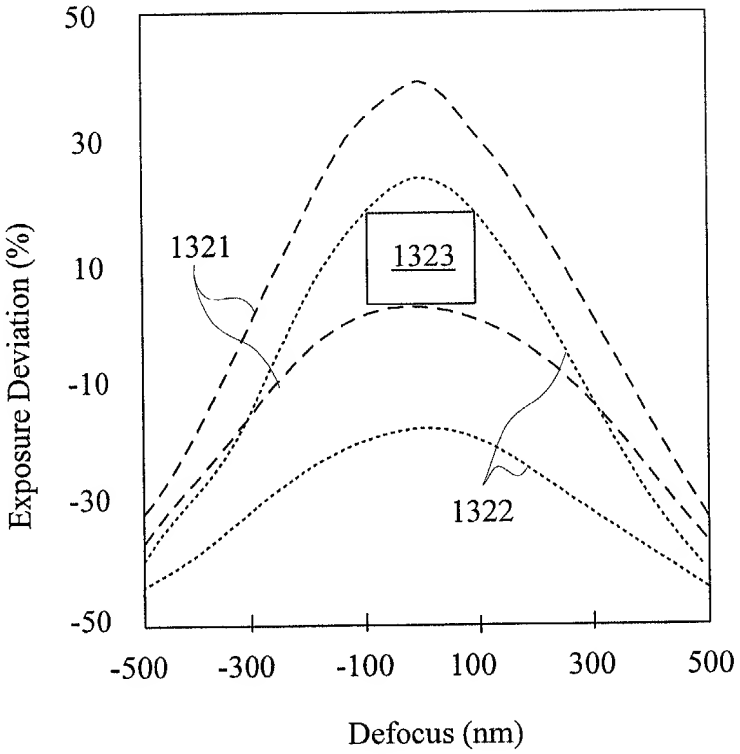


Figure 13B



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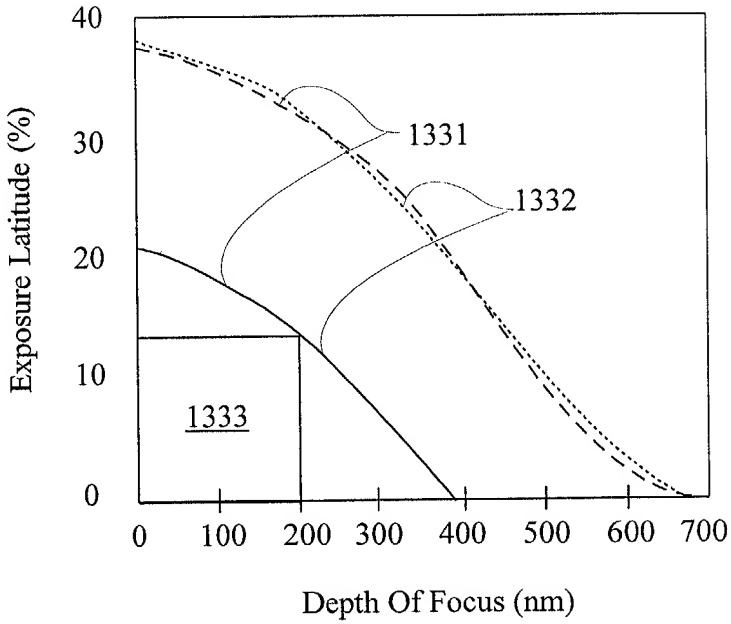

Figure 13D

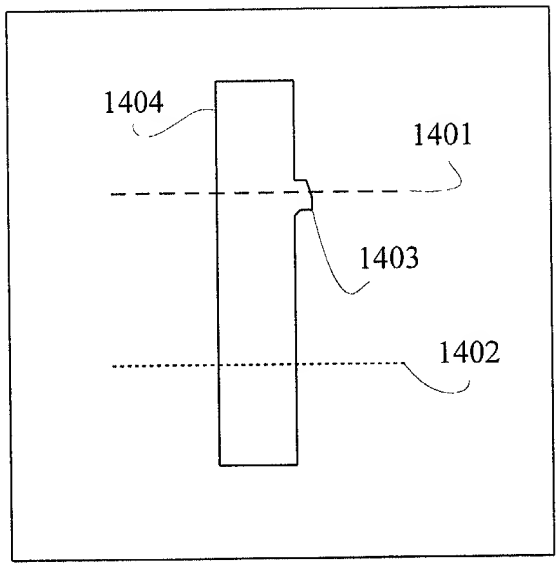

Figure 14A

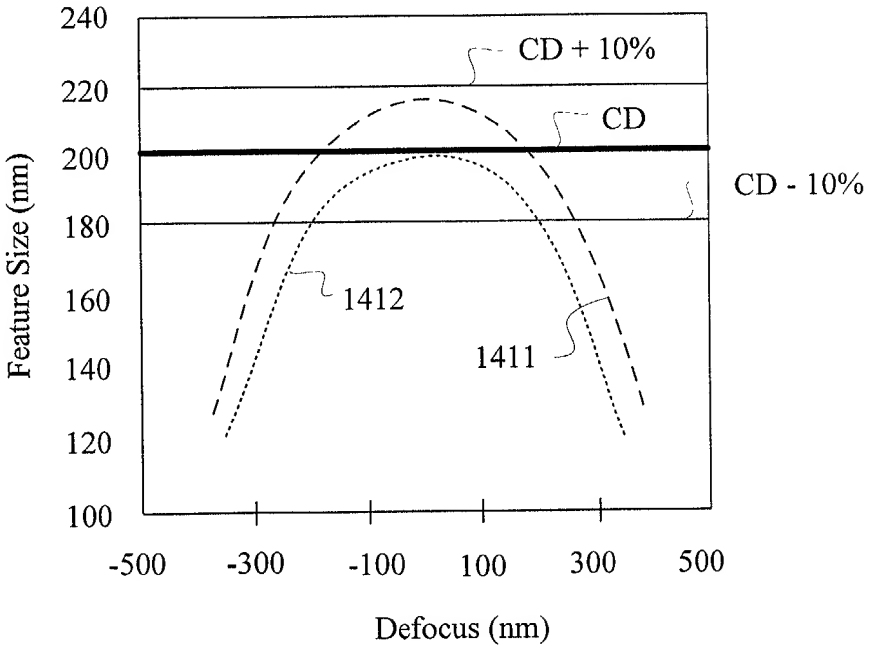

Figure 14B

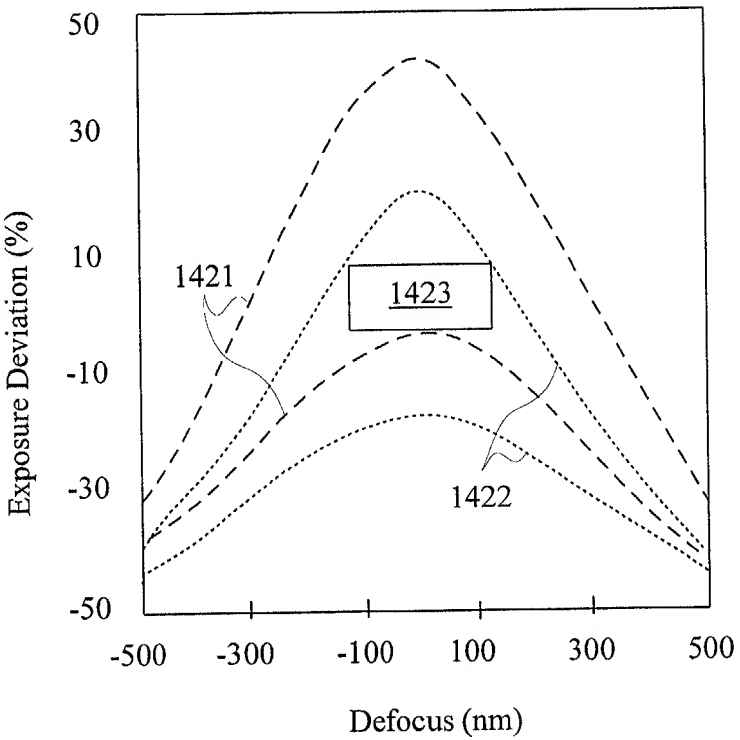

Figure 14C

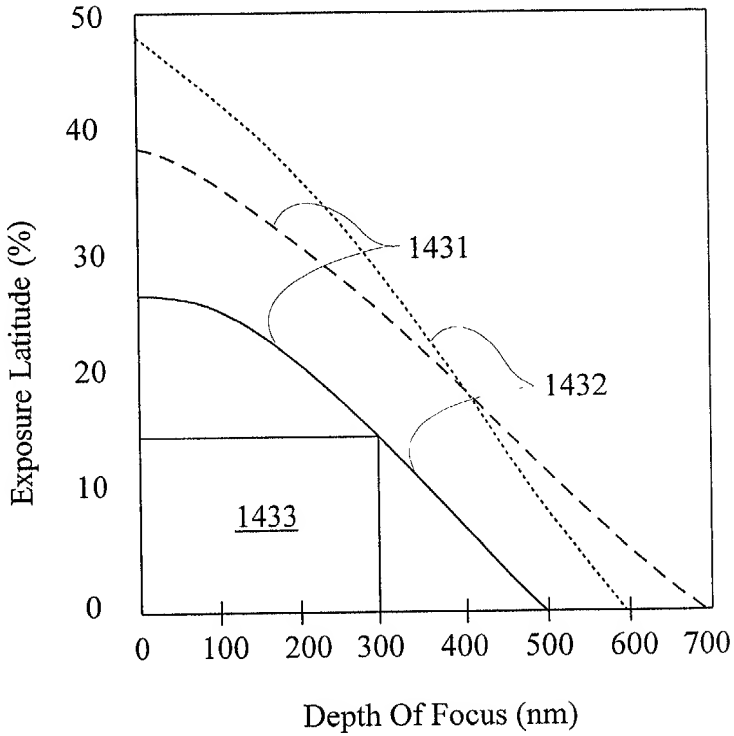

Figure 14D

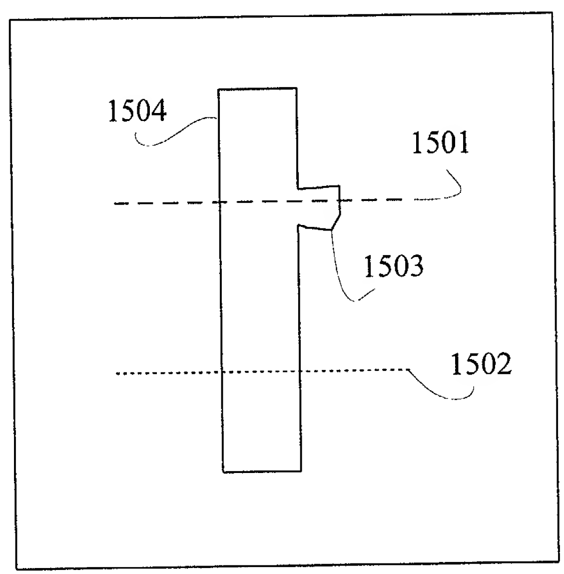

Figure 15A

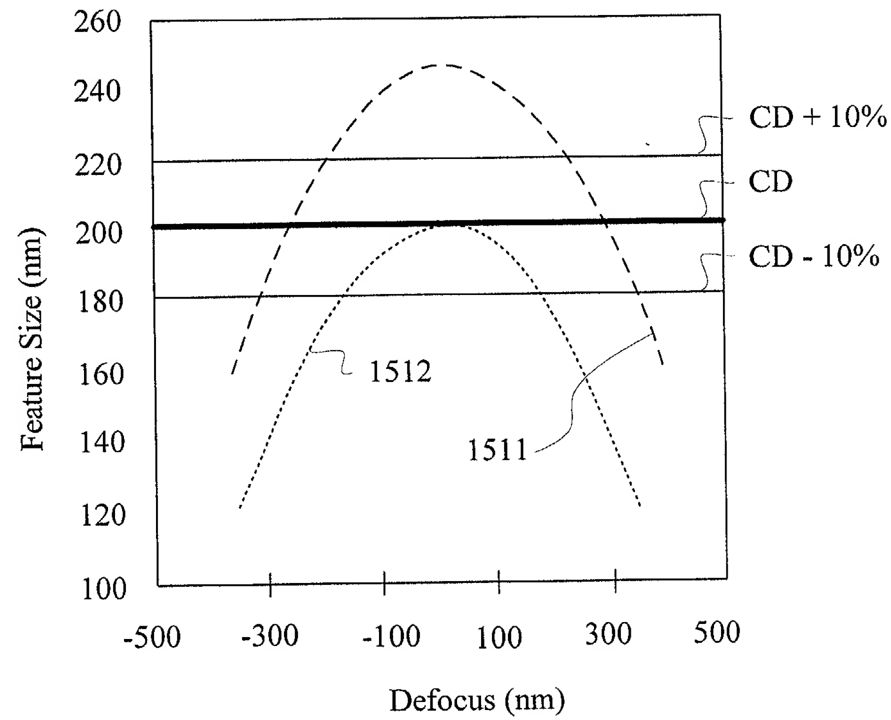

Figure 15B

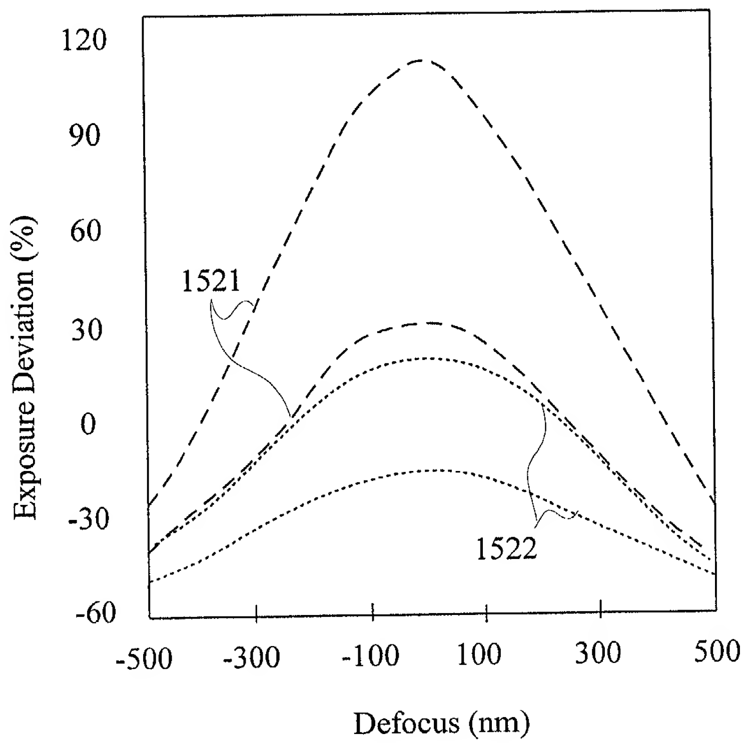

Figure 15C

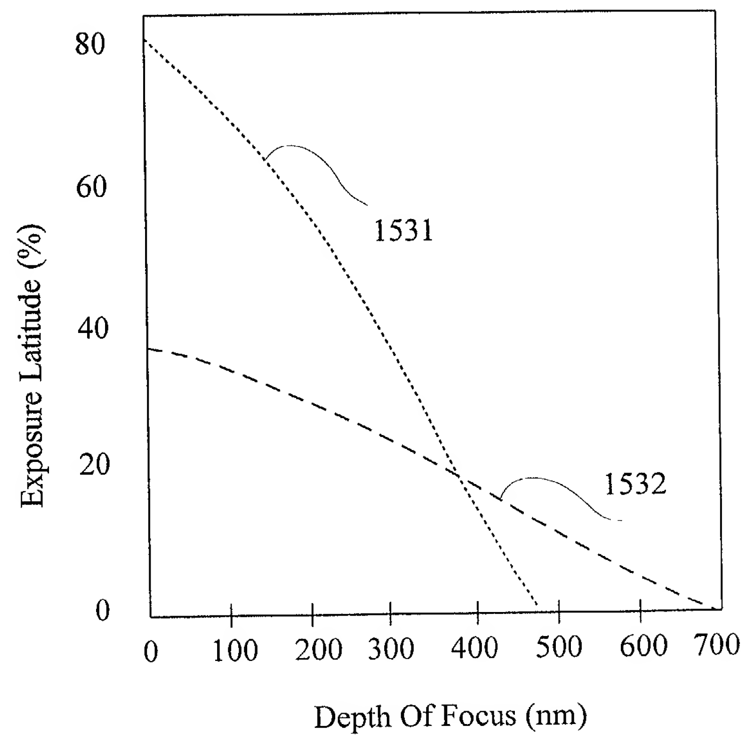

Figure 15D

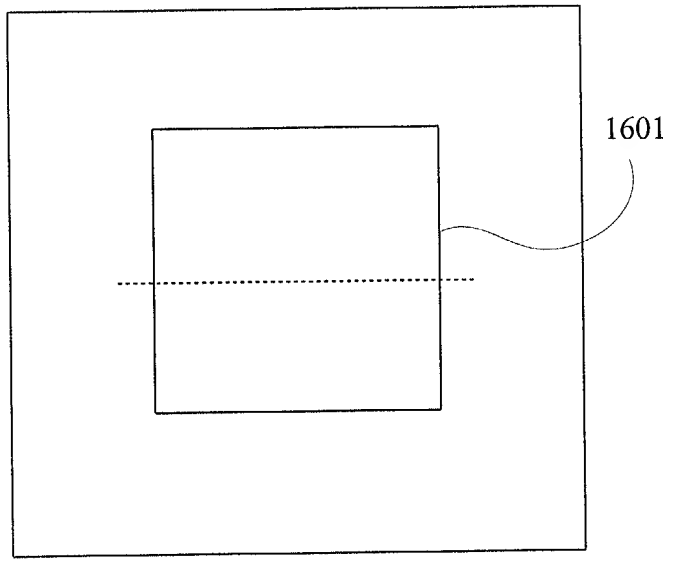

Figure 16A

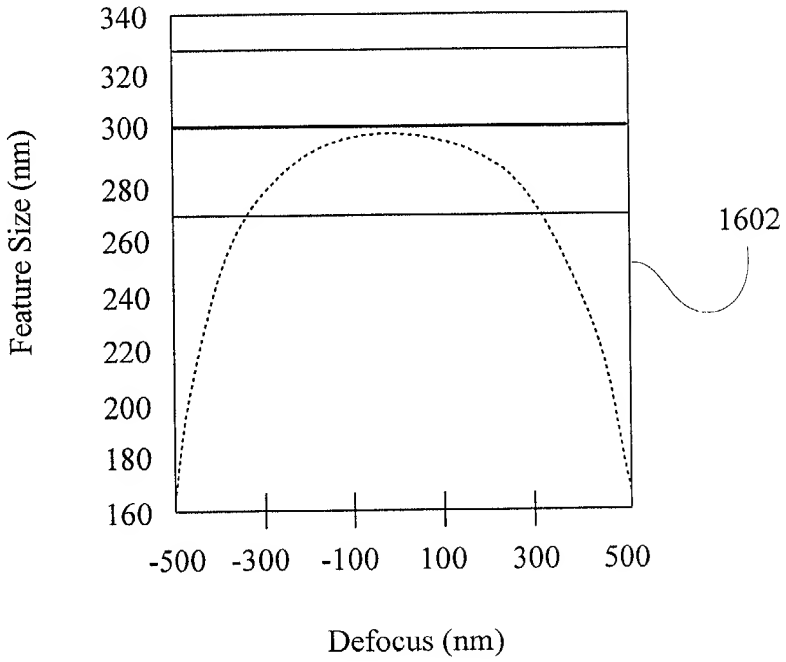

Figure 16B

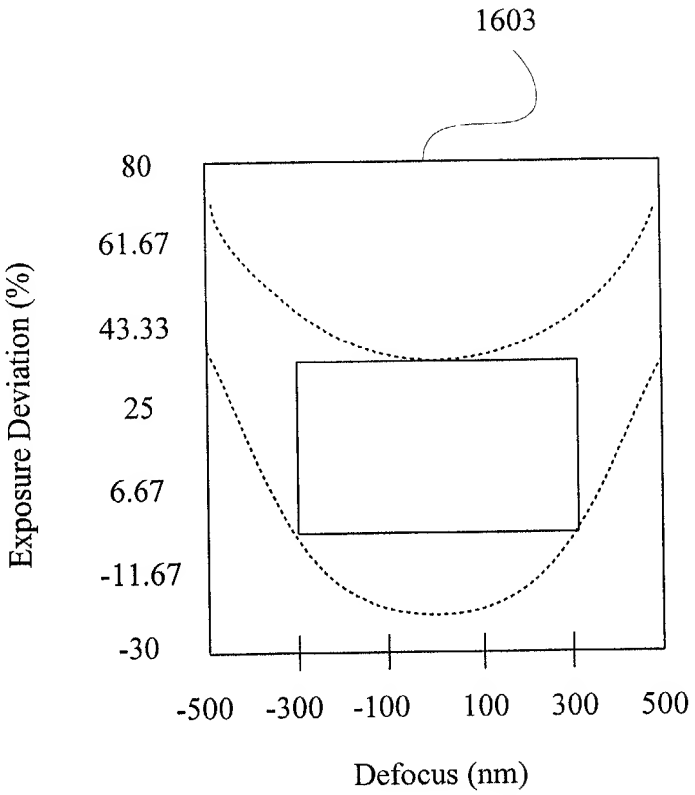

Figure 16C

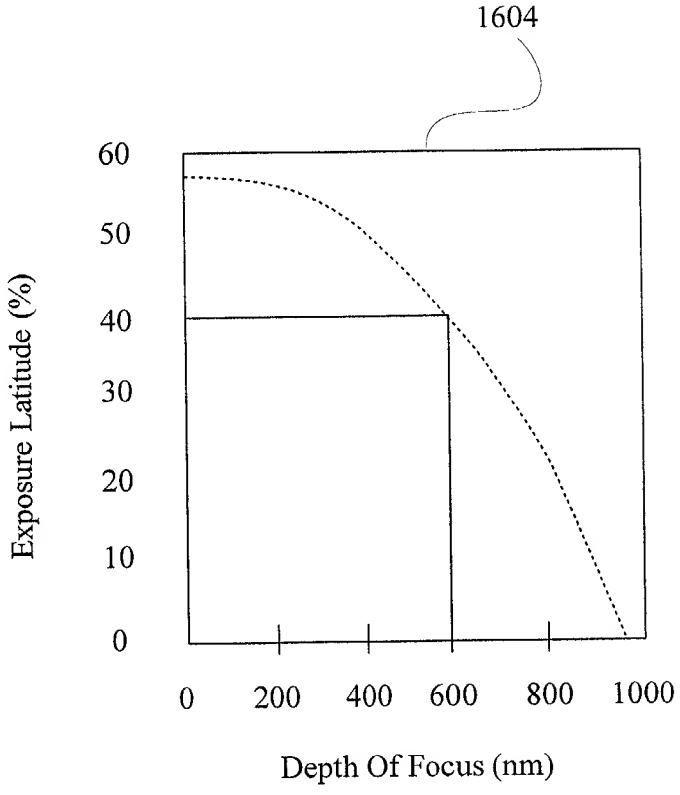

Figure 16D

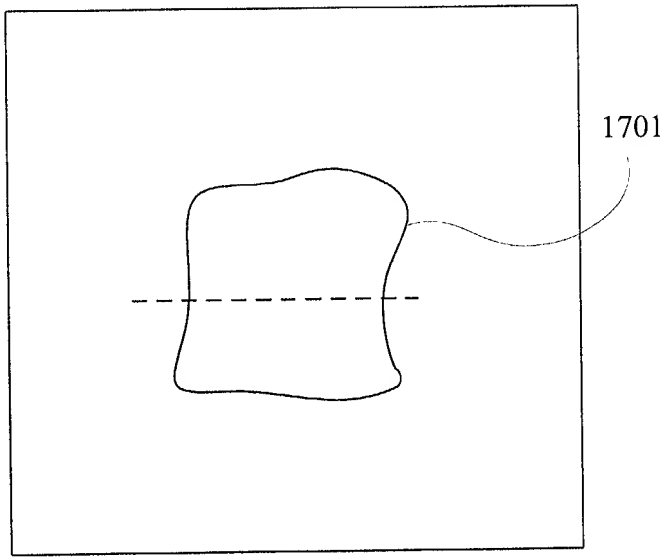

Figure 17A

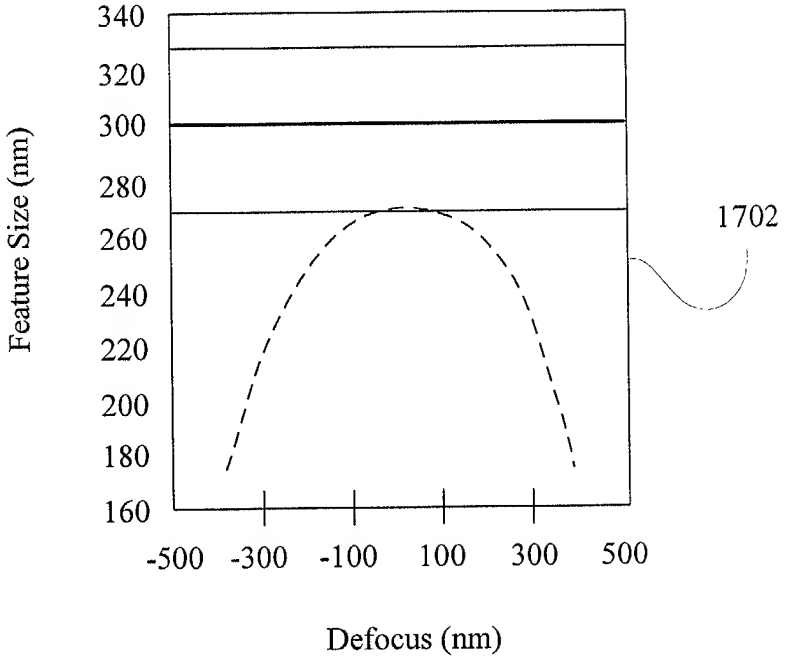

Figure 17B

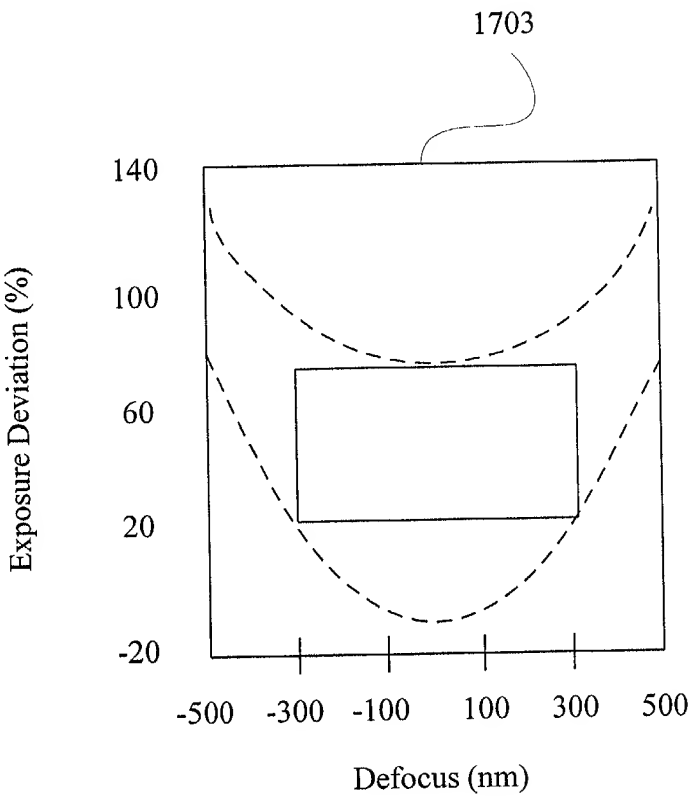

Figure 17C

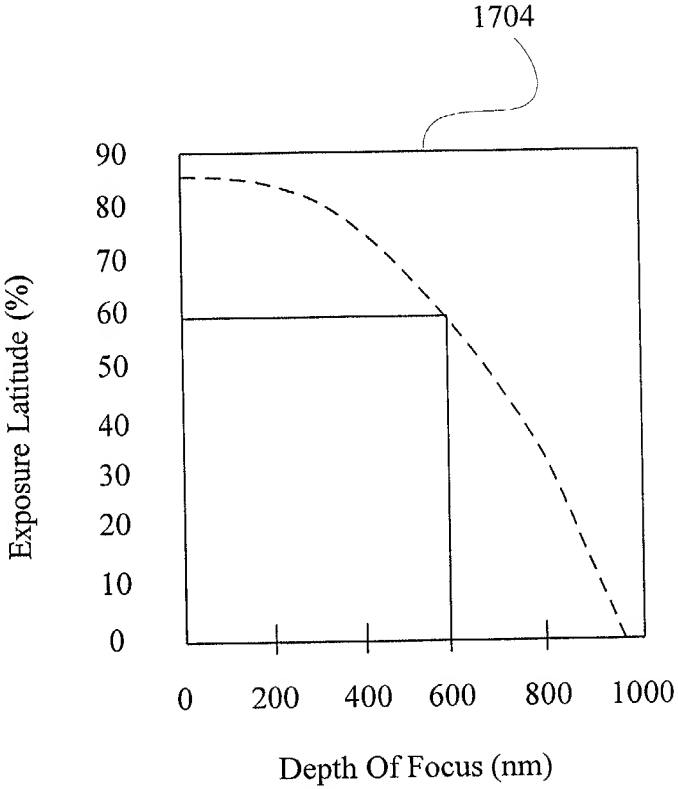

Figure 17D

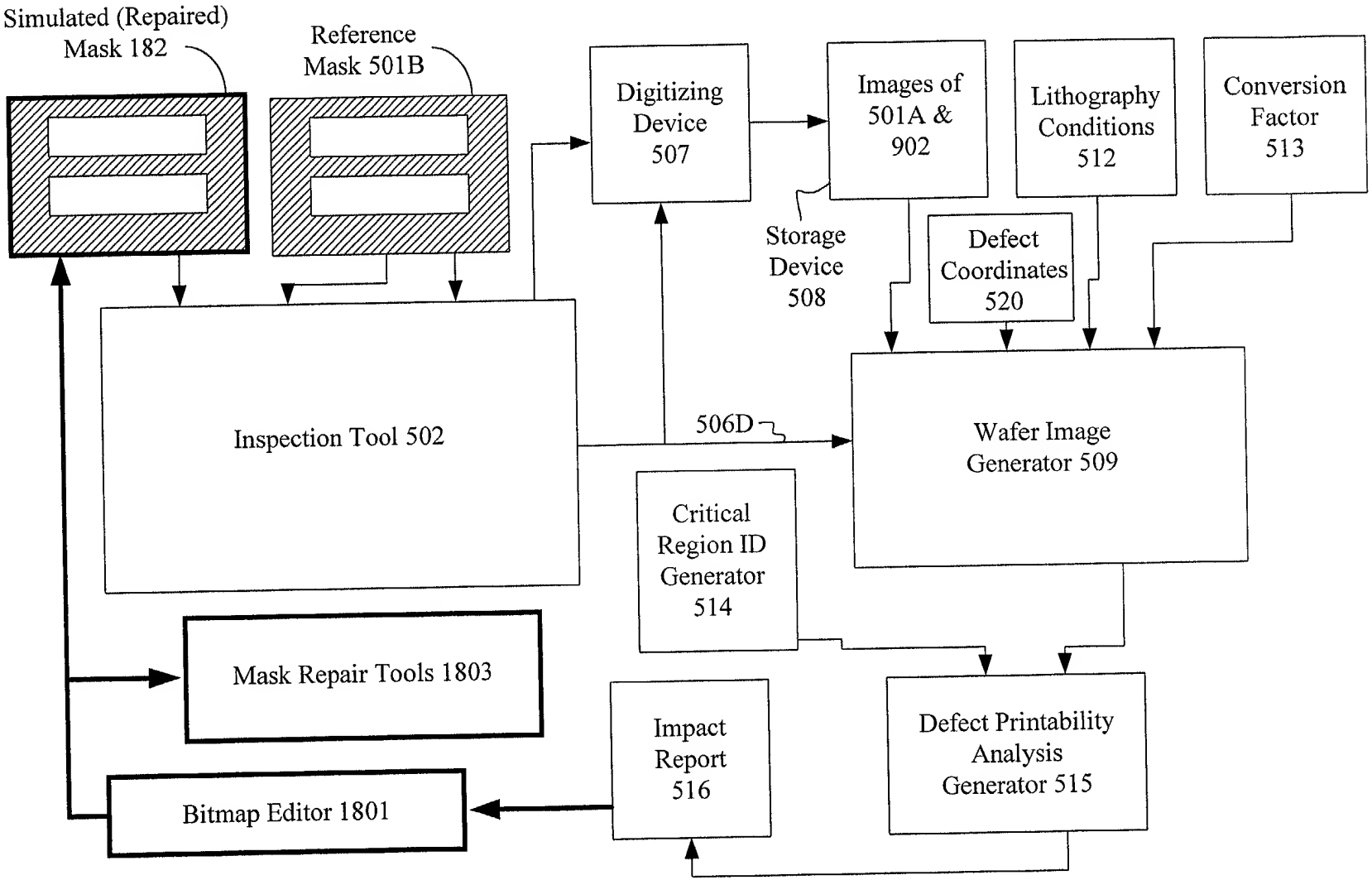
Simulated (Repaired) Mask 182
Reference Mask 501B
Digitizing Device 507
Images of 501A & 902
Lithography Conditions 512
Conversion Factor 513
Storage Device 508
Defect Coordinates 520
Inspection Tool 502
506D
Wafer Image Generator 509
Critical Region ID Generator 514
Mask Repair Tools 1803
Impact Report 516
Defect Printability Analysis Generator 515
Bitmap Editor 1801

Figure 18

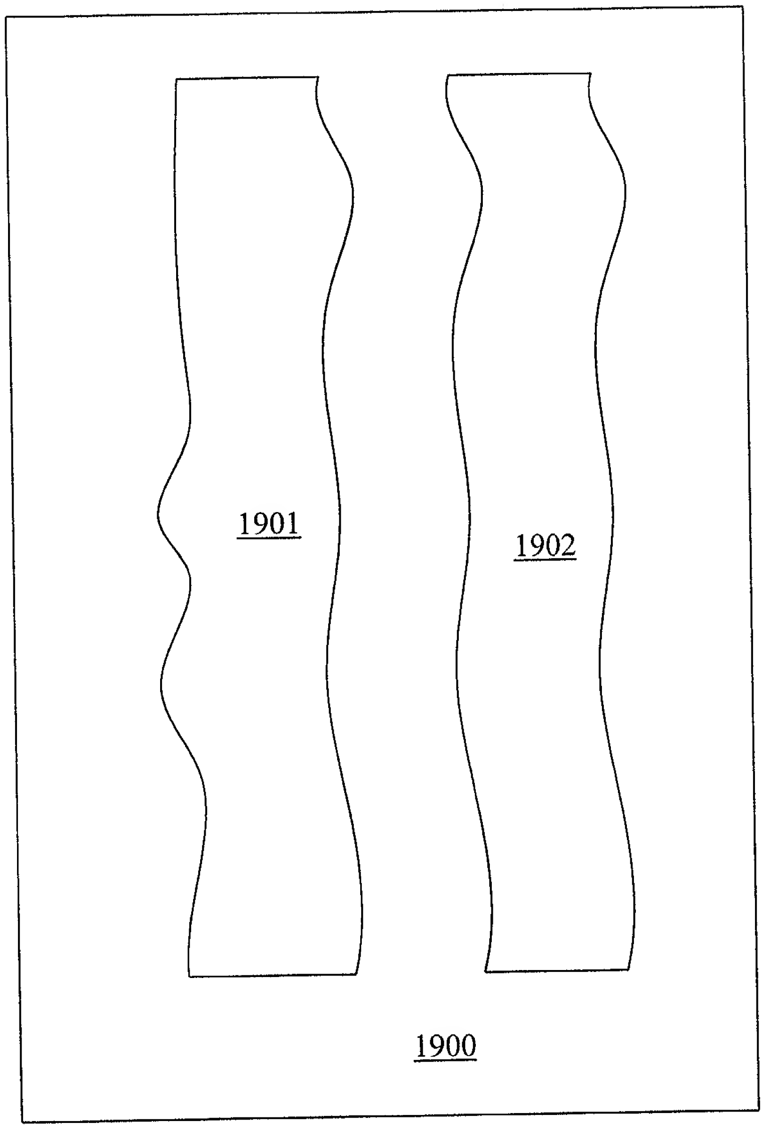

Figure 19A

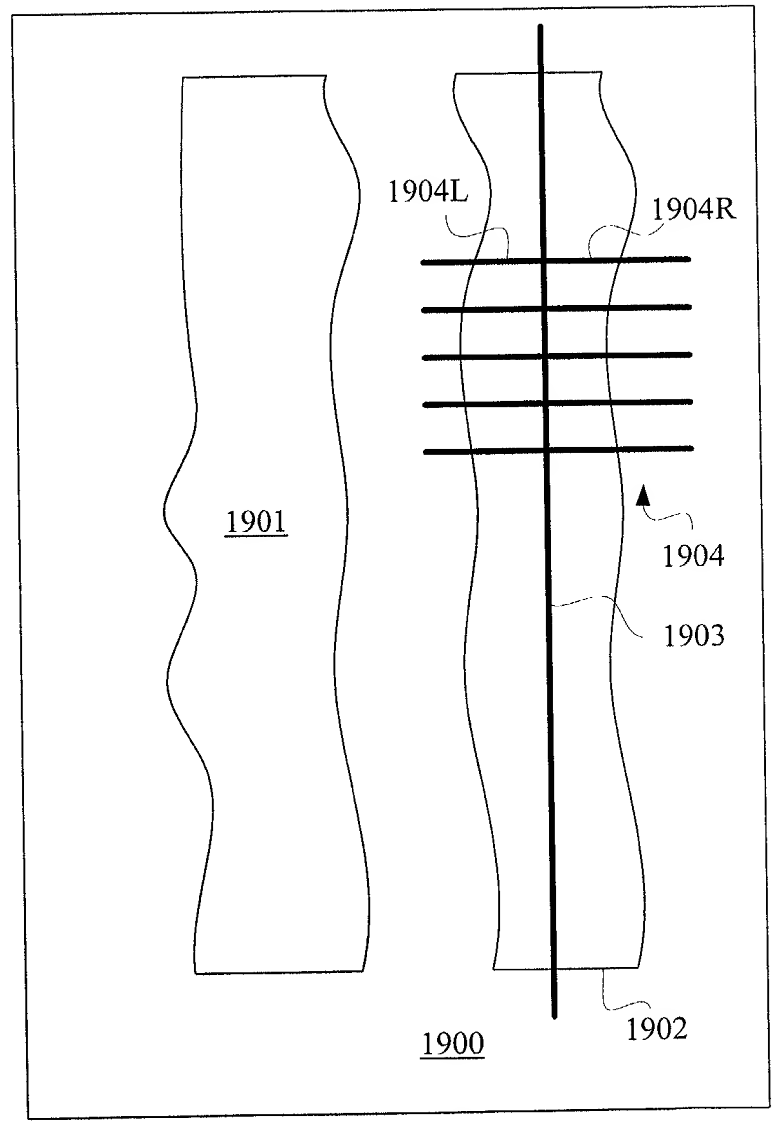

Figure 19B

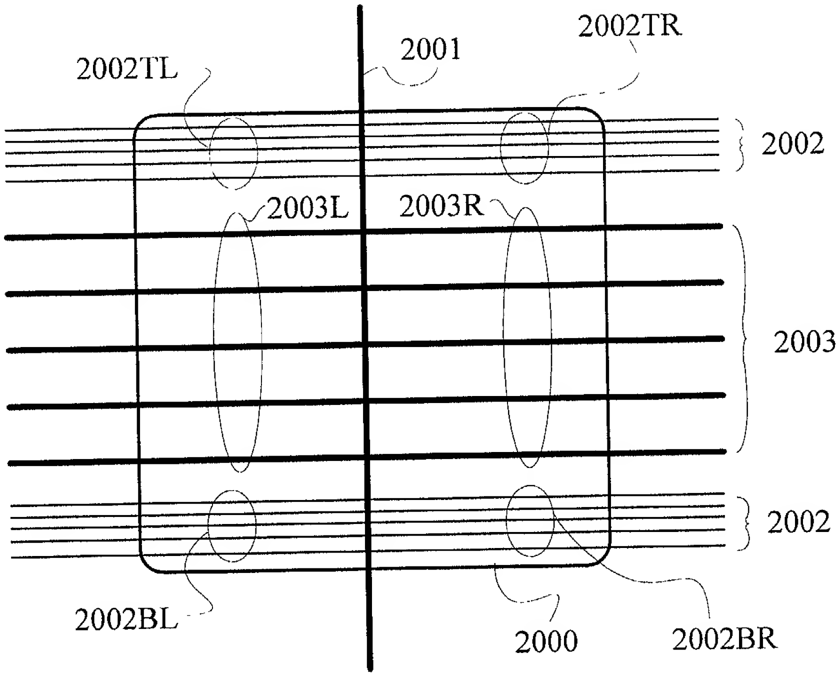

Figure 20A

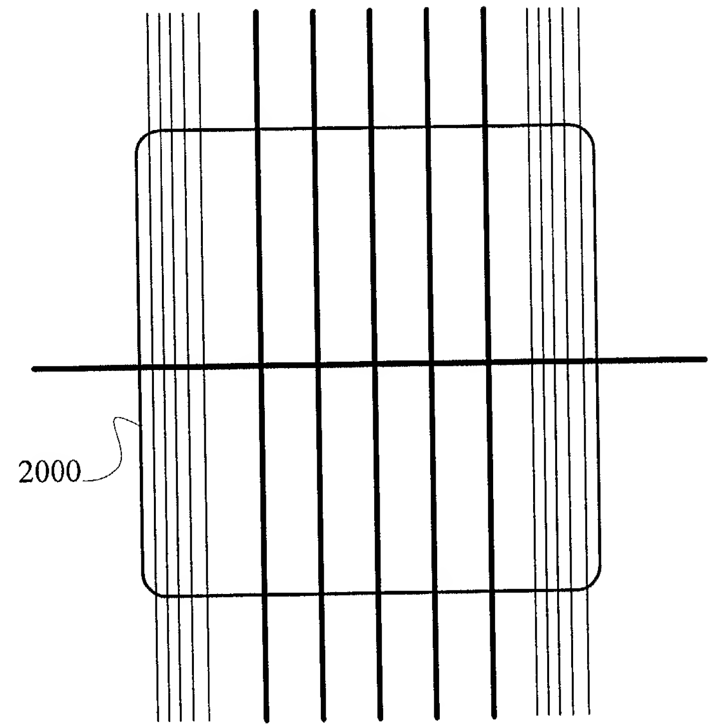

Figure 20B